

## AMENDMENTS TO THE CLAIMS

Please amend the claims as follows:

1. (Original)            A mask for transferring a lithographic pattern onto a substrate by use of a lithographic exposure apparatus, said mask comprising:  
                              at least one non-critical feature, formed utilizing one of a low-transmission phase-shift mask and a non-phase-shifting mask, and  
                              at least one critical feature, formed utilizing a high-transmission phase-shift mask.
2. (Original)            A mask according to claim 1, wherein said mask is formed on a single supporting plate.
3. (Original)            A mask according to claim 1, wherein said low-transmission phase-shift mask comprises a 5-8% transmission attenuated phase-shift mask.
4. (Original)            A mask according to claim 2, wherein said low-transmission phase-shift mask comprises a 5-8% transmission attenuated phase-shift mask.
5. (Original)            A mask according to claim 1, wherein said low-transmission phase-shift mask comprises a non-phase-shifting chrome mask.
6. (Original)            A mask according to claim 2, wherein said low-transmission phase-shift mask comprises a non-phase-shifting chrome mask.
7. (Original)            A mask according to claim 1, wherein said high-transmission phase-shift mask comprises at least a 10% transmission attenuated phase-shift mask.
8. (Original)            A mask according to claim 2, wherein said high-transmission phase-shift mask comprises at least a 10% transmission attenuated phase-shift mask.
9. (Original)            A mask according to claim 3, wherein said high-transmission phase-shift mask comprises at least a 10% transmission attenuated phase-shift mask.
10. (Original)           A mask according to claim 5, wherein said high-transmission phase-shift mask comprises at least a 10% transmission attenuated phase-shift mask.
11. (Original)           A mask according to claim 1, wherein said high-transmission phase-shift mask comprises at least a 10% transmission chromeless phase-shift mask.
12. (Original)           A mask according to claim 2, wherein said high-transmission phase-shift mask comprises at least a 10% transmission chromeless phase-shift mask.

13. (Original) A mask according to claim 3, wherein said high-transmission phase-shift mask comprises at least a 10% transmission chromeless phase-shift mask.
14. (Original) A mask according to claim 5, wherein said high-transmission phase-shift mask comprises at least a 10% transmission chromeless phase-shift mask.
15. (Original) A mask according to claim 1, wherein said mask comprises a plurality of said non-critical features and a plurality of said critical features.
16. (Original) A mask according to claim 3, wherein said mask comprises a plurality of said non-critical features and a plurality of said critical features.
17. (Original) A mask according to claim 5, wherein said mask comprises a plurality of said non-critical features and a plurality of said critical features.
18. (Original) A mask according to claim 7, wherein said mask comprises a plurality of said non-critical features and a plurality of said critical features.

**Claims 19-35 (Cancelled)**